# Apogee® 450 Spin Coater

## With DataStream™ Technology



Eliminate process variability from your critical experiments with the Cee® Apogee® 450 Spin Coater. This compact system delivers track-quality performance for processing large substrates with its durable, chemically compatible design and fully programmable, user-friendly operation. Guaranteed for years of high performance, the Cee® Apogee® 450 Spin Coater brings unparalleled consistency to your lab or fab.

Serving the Semiconductor Industry Since 1987

#### **BENEFITS**

- ETL Listed via Intertek's Nationally Recognized Testing Laboratory
- · Compact design for minimized footprint
- · Enhanced logging
- Vacuum and lid interlock
- DataStream<sup>™</sup> technology
- Durable benchtop design \*also available in a flange/ deck mountable configuration\*
- Optional X-Pro II workstation integrates equipment with an upper exhaust enclosure for process fume control.

#### **BOWL DESIGN**

- High-density polyethylene (HDPE) spin bowl for material compatibility
- Versatile lid design allows process flexibility and repeatability
- Optional nitrogen purge for an inert spin environment
- Integrated drain and exhaust ports

#### **PROGRAMMABILITY**

- Full-color touchscreen graphical user interface (GUI)
- Supports unlimited user-defined program steps for each recipe
- 0.1 second step time resolution (9,999.9 seconds maximum step time)
- Spin speeds up to 6,000rpm
- Spin speed acceleration up to 20,000rpm/s unloaded
- Up/download DataStream<sup>™</sup> process parameters via native USB and Ethernet ports
- · Multiple simultaneous automated dispense capability
- In-process dynamic speed & acceleration control



### **PRECISION**

- Substrate sizes: 300mm round; 14" x 14" square (max)
- Spin speed repeatability: 0.2rpm (per standard spin module)
- Spin speed resolution: 0.2rpm (per standard spin module)
- · Acceleration resolution <0.2rpm/s
  - 0 to 30,000 rpm/s unloaded
  - 0 to 23,000rpm/s with a typical 30mm silicon wafer
  - 0 to 3,000rpm/s with a 350mm x 6mm round recessed spin chuck
  - 0 to 400rpm/s with a 14" x 14" x 0.05" photomask in a recessed chuck

#### RELIABILITY

- · Industry leading uptime
- · 1-year full warranty on parts and labor
- Complimentary remote technical support for the life of the product
- Application process assistance for the life of the product
- Indirect drive system protects the spin motor from contact with process chemicals and solvents

#### **UTILITIES**

Voltage Ranges: 208-230VACPower Requirements: 6A max

Drain Port: 3/4" ODExhaust Port: 1" ODVacuum: <33kPa abs</li>

• Exhaust: 20-50cfm at 0.2" water

• N2/CDA (automated dispense): 70psi (482kPa)

#### **DIMENSIONS**

- 27 5/8" (702mm) W x 30 ¾" (781mm) D x 15 ½" (394mm) H
- machine weight 85lb (38.6kg) excluding accessories

## DATASTREAM™ TECHNOLOGY: CONNECTING THE SEMICONDUCTOR INDUSTRY

DataStream<sup>™</sup> technology gives you access to all of your connected Apogee® manufacturing equipment in one place to track, access, and modify your systems via a web browser. This technology provides manufacturers with the ability to process and visualize data in real time and search and export that data into a number of different formats.

#### Real-Time Process Information

- Constant feedback of process information for monitoring critical process parameters
- Streamlined interface between different process modules
- Visual cues on process status & health

#### **Advanced Recipe Creation**

- Seamless switching between basic and advanced recipe creation methods
- · Plain-English recipe translation
- Predefined process commands
- Unlimited process steps
- Unlimited recipe storage

#### **Environmental Monitoring**

- Monitoring of temperature & humidity allows for stricter control of critical processes
- Set preconditions and tolerances for monitored parameters
- On-screen, colored visual cues for deviation from controlled specs

#### **Data Logging & Export**

- Export data logs into commonly readable formats for further analysis and process troubleshooting
- Increase process efficiency
- Identify process control deviations
- Analyze multiple processes for best known method (BKM) development

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